

PREPARATION AND CHARACTERIZATION OF $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ VARISTOR CERAMICS BY HOT ISOSTATIC PRESSING (HIP) AND POST-ANNEALING

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Submitted July 1, 2020; accepted september 21, 2020

Keywords: Titanium oxide (TiO_2), Varistor ceramics, Nonlinear coefficient, Breakdown voltage, Hot Isostatic Pressing (HIP), Post-Annealing

$\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ varistor ceramics were prepared by hot isostatic pressing (HIP) and annealed in oxygen and nitrogen, respectively. The nonlinear coefficient α , the breakdown voltage E_B and the leakage current J_L of samples were tested using a varistor dc parameter meter. The average barrier height Φ_B of the unannealed samples and the samples annealed in oxygen and nitrogen was calculated. The microstructure of samples was analyzed by STEM-EDS, XRD and SEM. $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ varistor ceramics with uniform microstructure, fine grains and low porosity was obtained by HIP. By annealing, α increases, while E_B and J_L decrease. When annealing is performed in oxygen, the oxygen enrichment at the grain boundaries is also helpful to increase α and reduce J_L . $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ varistor ceramics with Ta_2O_5 and CaCO_3 contents of 0.20 mol. % sintered at 1200 °C and annealed at 700 °C for 3 h in oxygen possesses best varistor performance with $\alpha = 11.2$, $E_B = 22.6 \text{ V}\cdot\text{mm}^{-1}$ and $J_L = 8.7 \mu\text{A}\cdot\text{cm}^{-2}$.

INTRODUCTION

Because of nonlinear electrical behavior and sensitivity to instantaneous voltage fluctuations, varistor ceramics are widely used in circuits such as overvoltage protection, high voltage stability and high energy surge absorption [1-3]. The nonlinear behavior of a varistor is closely associated with the grain boundary barrier structure of polycrystalline ceramics [4]. Compared with other varistor ceramics, TiO_2 varistor ceramics have the advantages of low breakdown voltage and good dielectric performance, which can be used as a varistor-capacitor multifunctional material with simple preparation process and low cost [5-8]. Therefore they have a good application perspective [9-13]. But its nonlinear coefficient α (i.e. the ratio of static resistance to dynamic resistance at a point on an I-V curve) is generally quite low, which limits its practical application. Since TiO_2 ceramics was found to exhibit varistor characteristics in the Bell Labs in 1982 [4], researchers tried to improve its α value. Many works studied the effects of donor single doping, acceptor single doping and co-doping on the varistor properties [14-17].

Annealing is a heat treatment process in which samples are heated to a suitable temperature, kept for a period of time and then slowly cooled to obtain an equilibrated microstructure with required properties.

Annealing can stabilize size, adjust microstructure, eliminate defects and residual stress. Zheng et al. studied the effect of annealing on GaN-based semiconductor capacitors prepared by atomic deposition. The results suggest that the capacitance increases gradually as the annealing temperature increases from 300 to 500 °C [18]. Priyadarshini et al. studied the influence of the annealing environment on a SnO_2 thin film transistor deposited by the spin coating technique. The films are annealed at 500 °C for 1 h in different annealing ambient conditions with varying $\text{N}_2\text{:O}_2$ ratio. The results reveal that with the increase in nitrogen concentration the amount of defects in the films increases, but the device performance improves [19]. Hosokawa et al. studied the effect of annealing on the properties of Nd-Fe-Ti-B magnets. The results show that the magnetic properties can be improved by annealing for a short time at a temperature close to the crystallization temperature, while further annealing at a high temperature for a long time will lead to the deterioration of the magnetic properties [20]. Ramanjaneyulu et al. studied the reversible p-type properties of (P, N) co-doped ZnO films by pulse laser deposition. As the film grows, it changes from p-type to n-type within 120 days. Unannealed n-type films contain the donor impurities hydrogen and carbon, which are transformed into p-type semiconductors after annealing at 800 °C [21]. Li et al. studied annealing effects on the

structural and optical properties of TiO₂ films. The results show that the band gap of TiO₂ thin films decreases when the annealing temperature increases [22]. Mohsen et al. studied CaCu₃Ti₄O₁₂ (CCTO) thin films deposited by radio frequency magnetron sputtering and subsequently annealed at 300, 400, 500 or 600 °C. XRD analysis shows that the amorphous CCTO thin film transforms to a more crystalline structure as the annealing temperature increases to 600 °C [23].

In this work, in order to improve the nonlinear coefficient α of TiO₂ varistor ceramics, reduce the breakdown voltage E_B and the leakage current J_L , TiO₂-Ta₂O₅-CaCO₃ varistor ceramics were prepared by hot isostatic pressing (HIP) sintering and annealed in different atmospheres. After annealing the microstructure and varistor properties were investigated.

EXPERIMENTAL

The mixture was ground in a planetary ball mill to obtain the reactants. The purity of each reagent is as follows: TiO₂ (powder, 99.9 %), Ta₂O₅ (powder, 99.9 %), CaCO₃ (powder, 99.9 %). All reagents were obtained from Guanghua Sci-tech (China). Table 1 shows the initial doping content of the samples. According to the ratio of raw materials in Table 1, the mixture was ground for 10h with a mass ratio of 1:2:4 of powder to water blended with alcohol (water:alcohol = 3:1) to balls. After homogenization, each blend was dried at 90 °C for 10 h and de-agglomerated in a 400 mesh sieve. The obtained powder was isostatically pressed at 160 MPa into tablets (10 mm in diameter and 1mm thick). The tablets were degummed at 500 °C for 1 h in a box-type resistance furnace and cooled to room temperature. The degummed tablets were sintered for 2 h at 1100, 1150, 1200, and 1250 °C, respectively, in a hot isostatic pressing (HIP) furnace using nitrogen as the pressurizing medium. After

Table 1. Doping contents of samples.

Sample	Doping content (mol. %)		
	TiO ₂	Ta ₂ O ₅	CaCO ₃
#1	99.80	0.10	0.10
#2	99.60	0.20	0.20
#3	99.50	0.25	0.25
#4	99.40	0.30	0.30

Table 2. Electrical properties of samples with different sintering temperatures – E_B (V·mm⁻¹), J_L (μA·cm⁻²).

Sample	1100 °C			1150 °C			1200 °C			1250 °C		
	α	E_B	J_L	α	E_B	J_L	α	E_B	J_L	α	E_B	J_L
#1	4.8	31.2	14.6	5.7	30.2	13.4	6.5	25.5	12.9	6.1	24.3	13.1
#2	5.0	29.2	14.5	5.6	30.6	13.8	7.5	24.0	12.3	6.3	24.1	12.8
#3	5.1	28.0	14.2	6.2	28.5	13.1	7.1	24.3	12.7	6.9	23.5	12.0
#4	4.9	29.4	14.6	6.4	29.8	12.9	6.7	23.8	12.2	7.1	22.4	12.5

sintering the nitrogen was still injected in the furnace as a shielding gas during cooling. The samples obtained above were divided into three groups, the first group was not annealed, the second group was annealed in oxygen, and the third group was annealed in nitrogen. Each group of samples was submitted to the following procedures: ultrasonic cleaning with de-ionized water, XRD (Rigaku D/Max-2200, Japan) analysis, SEM (Philips XL30ESEM-TMP, Netherlands) observation, coating with silver electrodes on the two surfaces, testing varistor properties, making TEM samples, STEM (FEI Tecnai G2 TF30 S-Twin, USA) analysis. The varistor properties were characterized by testing the main parameters α , E_B and J_L using the varistor DC parameter meter (Huigao HG3516, China). The parameters for the XRD analysis are as follows: radiation CuK α , acceleration voltage 20 kV, scanning interval 0.5 °·min⁻¹ and step size 0.05 °·step⁻¹.

RESULTS

Experimental results

Table 2 shows the values of the nonlinear coefficient α , the breakdown voltage E_B and the leakage current J_L for different samples sintered at different temperatures. The sintering time of all samples was 2 h. As can be seen from Table 2, when the sintering temperature is 1200 °C, TiO₂-Ta₂O₅-CaCO₃ varistor ceramics have the relatively best varistor performance ($\alpha = 7.5$, $E_B = 24.0$ V·mm⁻¹, $J_L = 12.3$ μA·cm⁻² for sample #2). Subsequently, the varistor properties of sample #2 with a sintering temperature of 1200 °C were investigated after annealing in oxygen and nitrogen for 2, 2.5, 3, 3.5, and 4 h, respectively.

Table 3 shows the electrical properties of the samples sintered at 1200 °C for 2 h and annealed in oxygen and nitrogen at 600, 700, 800, and 900 °C for 2, 2.5, 3, 3.5, and 4 h, respectively, where #2O2 and #2N2 represent annealing in oxygen for 2 h and in nitrogen for 2 h, respectively; #2O3 and #2N3 represent annealing in oxygen and nitrogen for 3 h, respectively, and similar for #2O2.5, #2N2.5, #2O3.5, #2N3.5, #2O4, and #2N4. As can be seen from Table 3, the samples annealed at the same temperature for the same time in oxygen and nitrogen show slight differences in the nonlinear coefficient α and the breakdown voltage E_B . The sample #2O3 annealed at 700 °C for 3 h in oxygen

Table 3. Electrical properties of samples annealed in oxygen and in nitrogen – E_B ($\text{V}\cdot\text{mm}^{-1}$), J_L ($\mu\text{A}\cdot\text{cm}^{-2}$).

Sample	Time	600 °C			700 °C			800 °C			900 °C		
		α	E_B	J_L	α	E_B	J_L	α	E_B	J_L	α	E_B	J_L
#2O2	2 h	8.5	23.2	10.2	8.8	23.5	9.8	8.6	22.3	11.5	8.0	24.3	11.8
#2N2	2 h	8.1	24.5	10.8	8.8	24.2	10.2	8.7	23.5	11.2	8.3	23.6	10.9
#2O2.5	2.5 h	9.0	24.4	9.8	9.6	23.7	9.5	8.8	22.7	11.1	8.5	24.5	10.6
#2N2.5	2.5 h	9.3	24.1	9.8	9.4	23.5	9.5	9.0	24.5	10.9	8.5	22.8	10.7
#2O3	3 h	9.9	25.2	9.1	11.2	22.6	8.7	10.2	22.5	9.5	9.6	22.3	10.5
#2N3	3 h	9.6	24.9	9.3	10.9	20.5	8.9	10.0	23.1	9.8	9.5	24.1	10.9
#2O3.5	3.5 h	9.6	23.7	9.5	10.5	21.9	9.2	9.8	21.5	10.2	9.0	21.6	11.3
#2N3.5	3.5 h	9.4	24.0	9.6	10.5	21.7	8.8	9.6	20.9	10.3	9.2	23.7	11.0
#2O4	4 h	9.1	24.3	9.8	10.1	22.5	9.4	9.4	23.0	10.5	9.1	22.9	11.4
#2N4	4 h	8.9	24.5	10.5	10.2	23.4	9.6	9.5	21.8	10.5	8.7	24.0	11.5

(denoted #2O73 in the sequel) has the best varistor performance with $\alpha = 11.2$, $E_B = 22.6 \text{ V}\cdot\text{mm}^{-1}$ and $J_L = 8.7 \mu\text{A}\cdot\text{cm}^{-2}$, which is superior to previous findings [24-26]. The sample #2N3 annealed at 700 °C for 3 h in nitrogen (denoted #2N73 in the sequel) has comparable performance with $\alpha = 10.9$, $E_B = 20.5 \text{ V}\cdot\text{mm}^{-1}$, and $J_L = 8.9 \mu\text{A}\cdot\text{cm}^{-2}$. #2O73 and #2N73 are both superior to the unannealed sample #2. The result showed that annealing significantly improves the varistor performance of $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ varistor ceramics. With the increase of the annealing temperature and the annealing time, the α value starts to decrease, which indicates that the annealing temperature and the annealing time have a significant influence on the varistor performance of the samples.

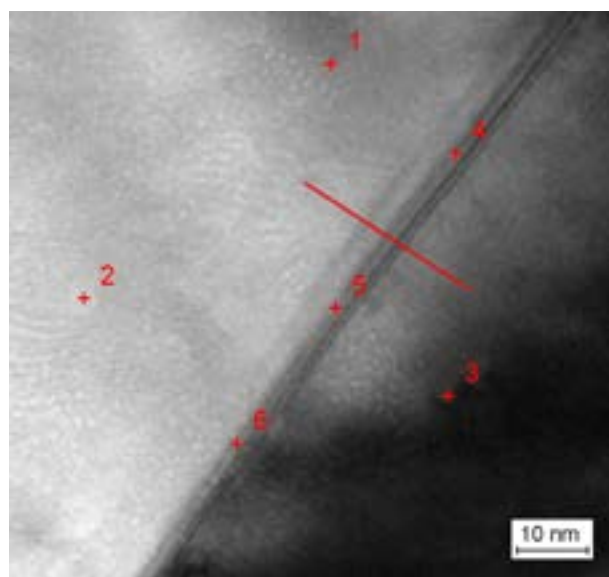
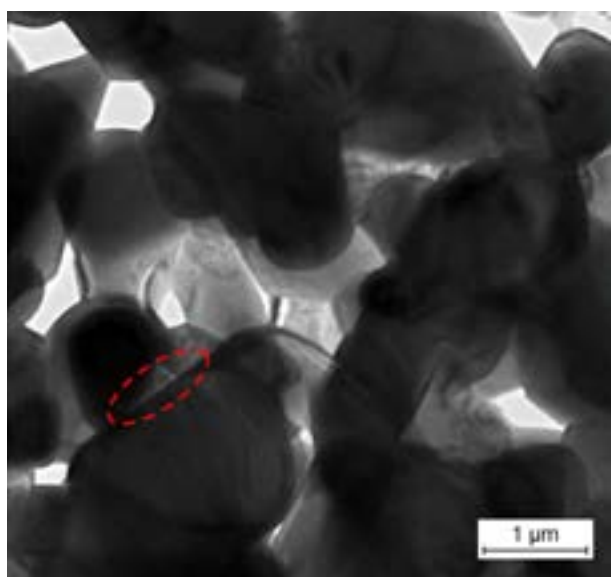
The average barrier height Φ_B of grain boundary of unannealed samples and samples annealed in oxygen and nitrogen is listed in Table 4. Φ_B was calculated via the formula

$$J = A^* T^2 \exp [(\beta E^{1.2} - \Phi_B) / k T_K],$$

where A^* and k represent the Richardson constant and the Boltzmann constant, respectively, and T_K represents the absolute temperature. The two groups of electric current J and electric field E were tested at the same temperature. The values of β and Φ_B were calculated. Three Φ_B values were obtained and the average Φ_B was calculated for each sample.

 Table 4. Effect of annealing on grain boundary barrier Φ_B (eV).

Sample	unannealed	600 °C	700 °C	800 °C	900 °C
#2	0.58	–	–	–	–
#2O3	–	0.89	1.49	1.41	1.37
#2N3	–	0.85	1.38	1.35	1.32



a)

 Figure 1. STEM-EDS images of $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ ceramics: a) unannealed (#2), annealed at 700 °C for 3 h in oxygen (b) (#2O73) and nitrogen (c) (#2N73). (Continue on next page)

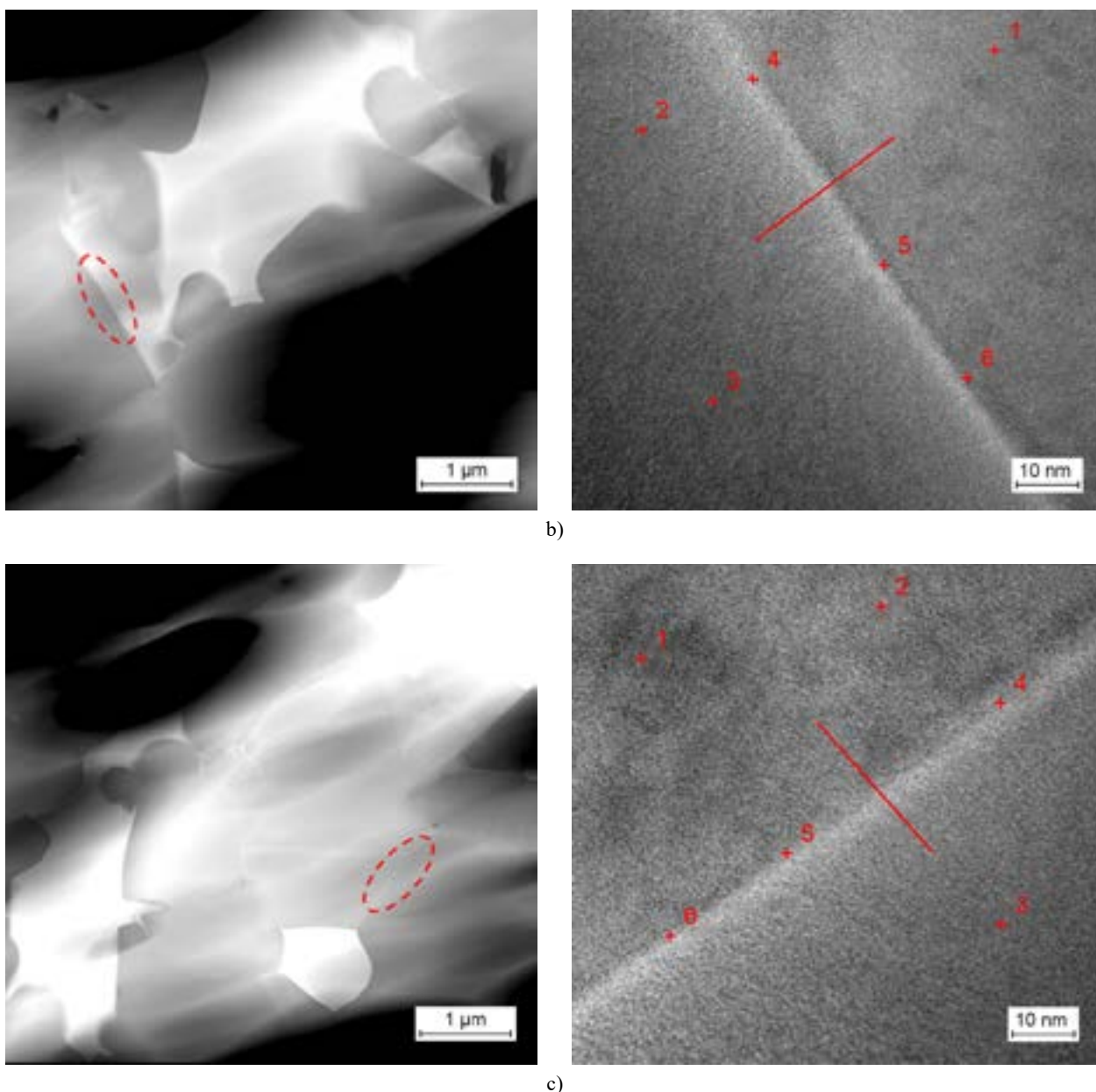


Figure 1. STEM-EDS images of $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ ceramics: b) annealed at 700 °C for 3 h in oxygen (#2O73), c) nitrogen (#2N73).

STEM spot scanning analysis

Figure 1 is STEM-EDS (X-ray energy dispersive spectroscopy, in the sequel abbreviated as EDS) images of samples #2 (a), #2O73 (b) and #2N73 (c). The points 1, 2 and 3 are located inside the grains, while the points 4, 5 and 6 are located at grain boundaries in the figures. The element contents of each point are listed in Table 5. By analyzing element contents of the analyzed points, the contents of Ca at grain boundaries are found to be higher in the annealed samples #2O73 and #2N73 than in the unannealed sample #2. As expected, the O content of sample #2O73 is higher than that of sample #2 and #2N73 at the grain boundaries. Ca^{2+} ions are likely to be segregated at the grain boundary due to their large size. So the content of Ca^{2+} of the samples annealed in

oxygen and nitrogen tends to decrease inside the grains, and tends to increase at the grain boundaries. Due to annealing in oxygen, the oxygen is of course enriched at the grain boundaries [27]. The nonlinear coefficient α of the annealed samples #2O73 and #2N73 is higher than that of the unannealed sample #2, which is mainly because the concentration of acceptor ions Ca^{2+} at the grain boundaries increases during annealing, thus increasing the acceptor density at the grain boundaries and the height of the grain boundary potential barrier. The α value of sample #2O73 is slightly higher than that of sample #2N73 due to oxygen enrichment at the grain boundaries that also increases the acceptor density and the height of grain boundary potential barrier during annealing.

Table 5. Element contents inside grains and at grain boundaries of sample unannealed (#2), annealed at 700 °C for 3 h in oxygen (#2O73) and annealed at 700 °C for 3 h in nitrogen (#2N73).

Position	Element (at. %)											
	OK			TiK			TaK			CaK		
	#2	#2O73	#2N73	#2	#2O73	#2N73	#2	#2O73	#2N73	#2	#2O73	#2N73
1	73.89	73.65	73.03	25.79	25.74	26.84	0.23	0.53	0.08	0.09	0.08	0.05
2	68.02	70.64	67.62	31.46	29.21	32.07	0.34	0.06	0.19	0.18	0.09	0.12
3	69.90	72.64	77.69	29.45	27.00	21.86	0.49	0.21	0.38	0.16	0.15	0.07
4	71.36	73.16	72.70	28.37	26.43	26.77	0.40	0.08	0.25	0.23	0.33	0.28
5	69.58	70.80	68.55	30.09	28.36	30.95	0.07	0.43	0.12	0.26	0.41	0.38
6	70.96	71.04	67.18	28.39	28.51	32.18	0.35	0.17	0.39	0.30	0.28	0.25

STEM line scanning analysis

Figure 2 shows the line scan graphs of samples #2, #2O73 and #2N73 across the grain boundary. As can be seen from the figure, after annealing the content of Ca at the grain boundary is relatively higher; the oxygen content increases slightly at the grain boundary of sample #2O73 annealed in oxygen. The grain boundary width of sample #2O73 and #2N73 was estimated to be about

4.5 nm and 5.0 nm, based on the Ca content at the grain boundary.

XRD analysis

Figure 3 shows the XRD patterns of samples #2 (a), #2O73 (b) and #2N73 (c). It can be seen from Figure 3 that no diffraction peak of second phase is found after

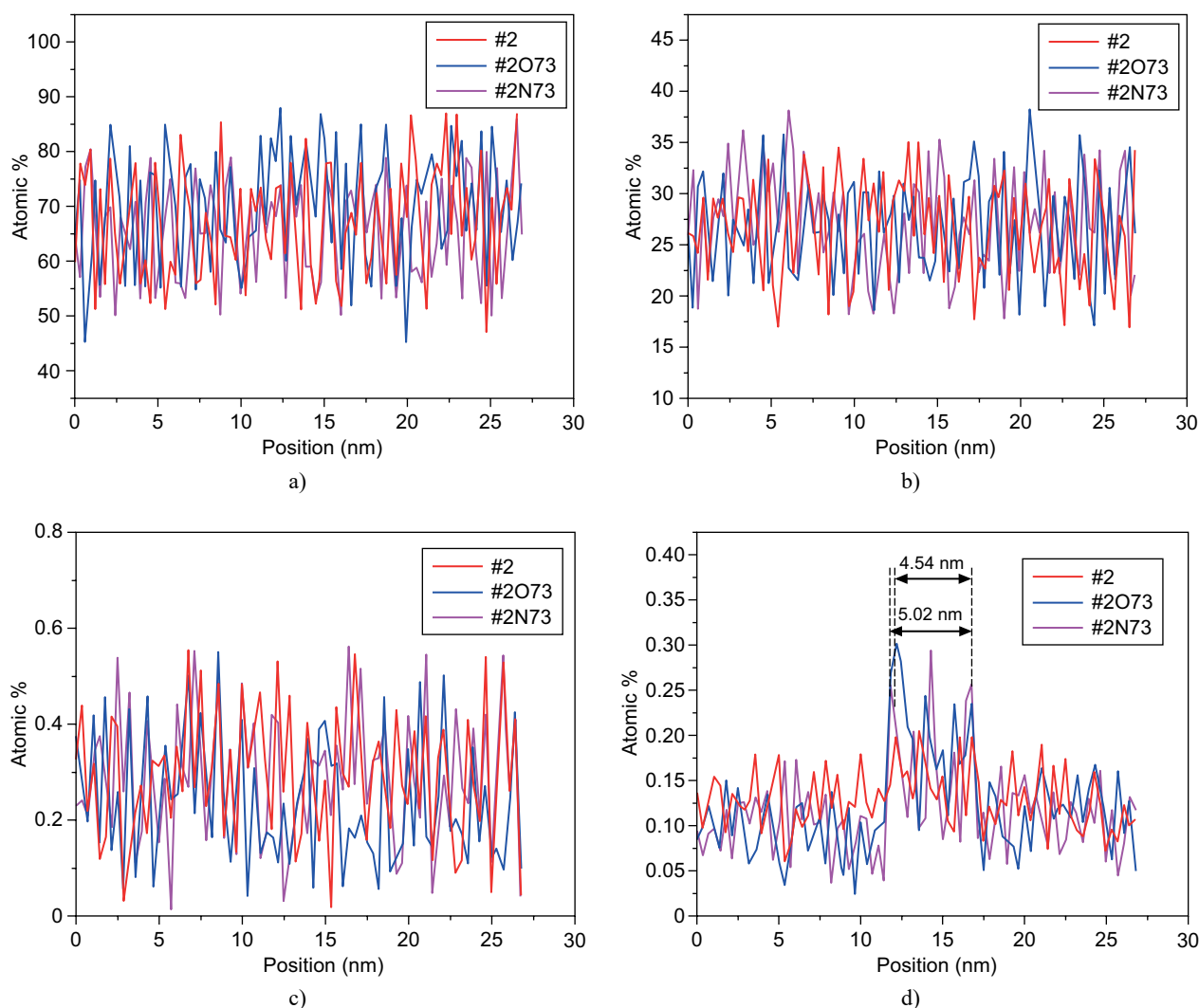


Figure 2. Line scan graphs of sample #2, #2O73 and #2N73 across grain boundaries.

annealing in oxygen or nitrogen. The diffraction peaks of sample #2O73 annealed in oxygen or #2N73 annealed in nitrogen are relatively smoother compared to those of the unannealed sample #2, and the strength of background peaks of #2O73 and #2N73 is significantly lower than that of #2. Table 6 shows the correlation parameters

of the strongest diffraction peaks near $2\theta = 27.5^\circ$ for samples #2, #2O73 and #2N73. The diffraction peak intensity increases and the full width at half maximum (FWHM) decreases slightly in samples #2O73 and #2N73, indicating that the grains (crystallites) are well developed and essentially free of micro strain.

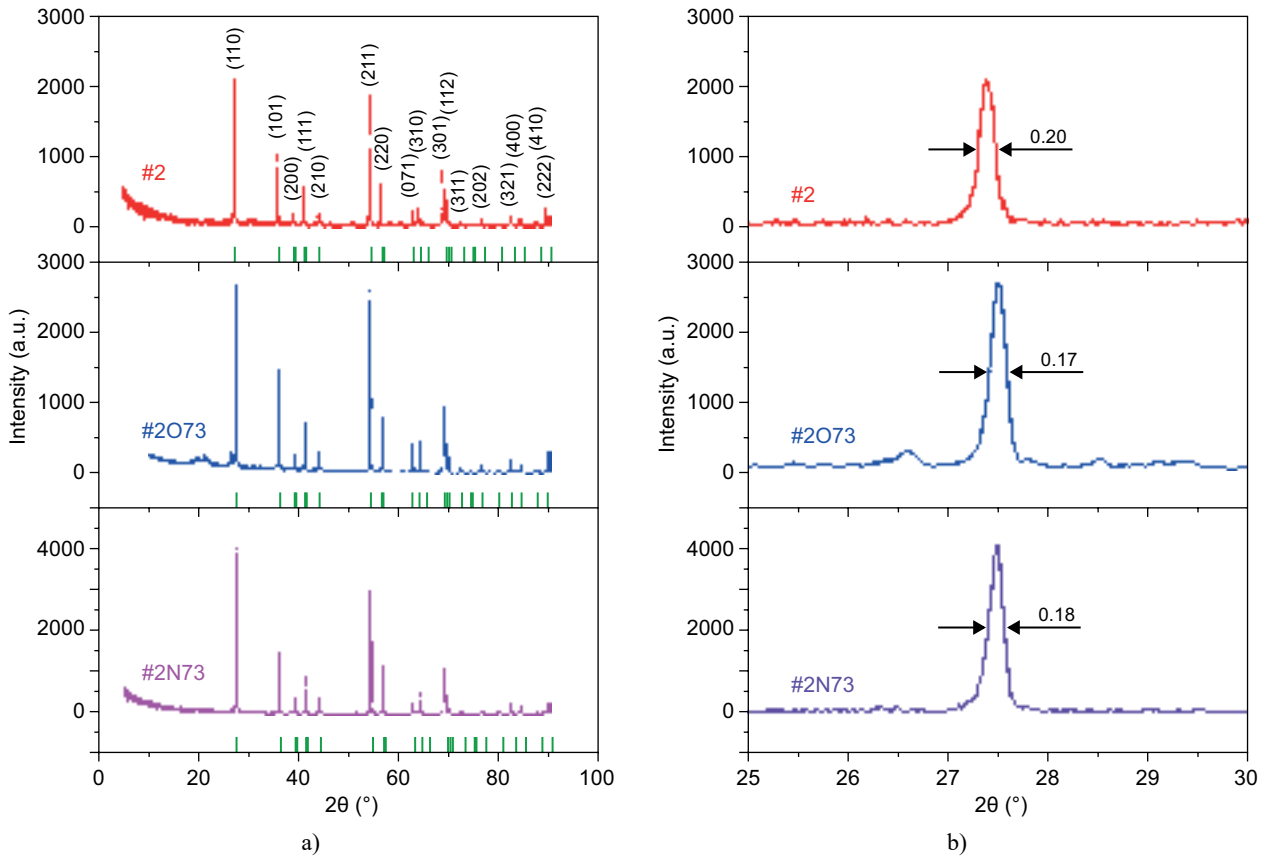


Figure 3. XRD patterns of $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ ceramics unannealed (#2), annealed at 700 °C for 3 h in oxygen (#2O73) and nitrogen (#2N73).

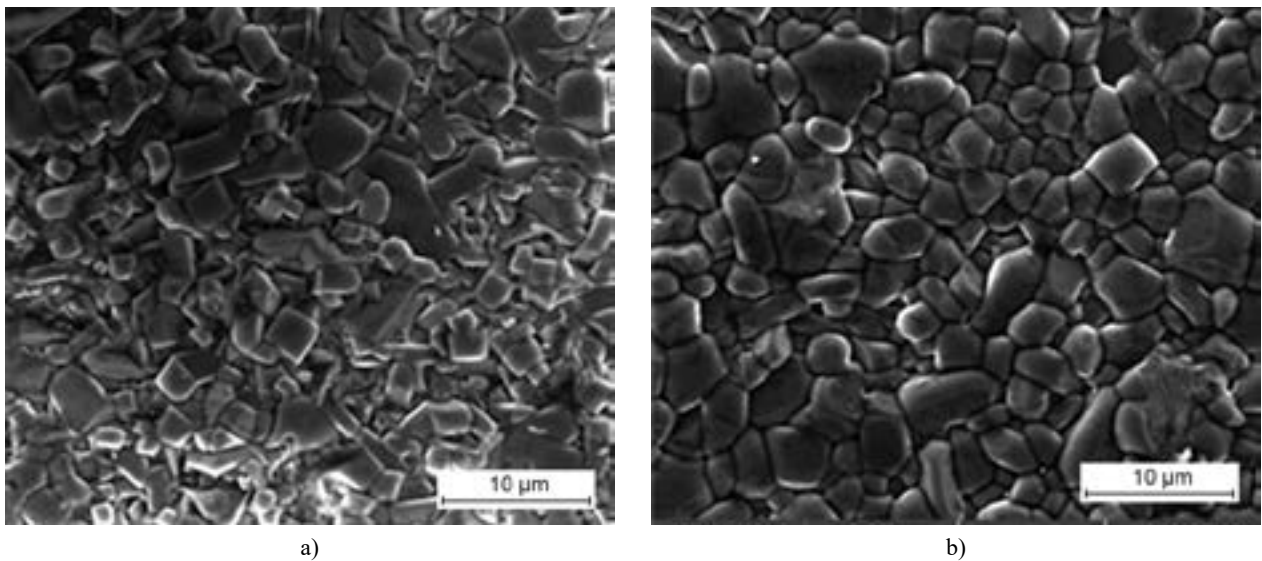


Figure 4. SEM images of $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ ceramics: a) by HIP sintering and unannealed (#2), b) by HIP sintering and annealed at 700 °C for 3 h in oxygen (#2O73). (Continue on next page)

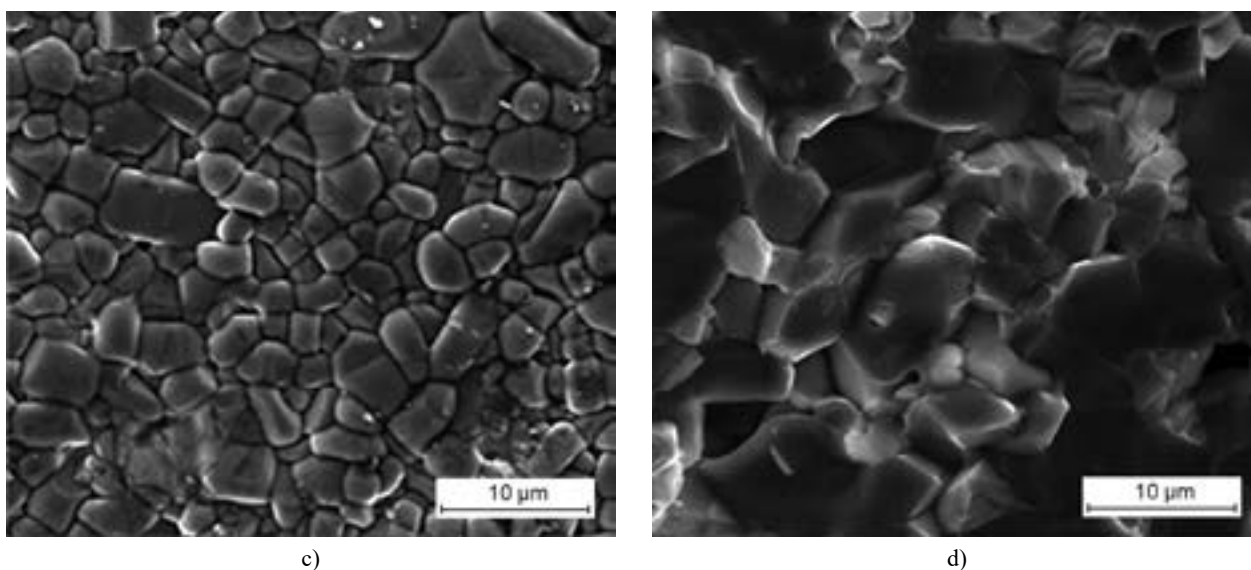


Figure 4. SEM images of $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ ceramics: c) by HIP sintering and annealed at 700°C for 3 h in nitrogen (#2N73), d) by pressureless sintering and unannealed.

Table 6. Diffraction peak change near $2\theta = 27.5^\circ$ of sample unannealed (#2), annealed at 700°C for 3 h in oxygen (#2O73) and annealed at 700°C for 3 h in nitrogen (#2N73).

Sample	2θ ($^\circ$)	Peak height	FWHM ($^\circ$)
#2	27.38	2124.51	0.20
#2O73	27.51	2743.66	0.17
#2N73	27.49	4012.96	0.18

SEM analysis

Figure 4 shows SEM micrographs of samples #2 (a), #2O73 (b), and #2N73 (c). From Figures 4a-c it is evident, that the grain structures of the three samples are relatively dense and the porosity is very low. Comparing (a), (b) and (c), it can be seen that the grains of samples #2O73 and #2N73 are bigger with a more uniform size than those of the unannealed sample #2, which is conducive to good electrical properties.

CONCLUSION

Hot isostatic pressing (HIP) and post-annealing can improve the microstructure of $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ varistor ceramics. Using HIP $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ varistor ceramics with uniform microstructure, fine grain and low porosity can be obtained. During annealing, the acceptor ions Ca^{2+} with larger radius are further segregated towards the grain boundaries, which increases the density of acceptor state and the height of the potential barrier at the grain boundaries. Therefore the nonlinear coefficient α increases. After annealing in the oxygen, the oxygen enrichment at the grain boundaries is also helpful to increase the grain boundary potential barrier, thus further increasing the α value. Increasing the grain

boundary barrier reduces the background current, thus reducing the leakage current J_L . Annealing at a suitable temperature for a suitable time can make the grains grow appropriately and the grain size uniform, which results in a decrease of the number of grain boundaries and the total area of grain boundaries. Therefore the breakdown voltage E_B tends to decrease. As the doping content of Ta_2O_5 and CaCO_3 is 0.20 mol. %, respectively, and the sintering temperature is 1200°C , $\text{TiO}_2\text{-Ta}_2\text{O}_5\text{-CaCO}_3$ varistor ceramics annealed at 700°C for 3 h in oxygen possesses the best varistor performance, with $\alpha = 11.2$, $E_B = 22.6 \text{ V}\cdot\text{mm}^{-1}$ and $J_L = 8.7 \mu\text{A}\cdot\text{cm}^{-2}$.

Acknowledgements

The present work was supported by the Agricultural Joint Programs of Yunnan Province [grant number 2018FG001-063], the University-Level Research Project [grant number 112004], the Applied Basic Research Programs of Yunnan Province [grant number 2019FB067], the Training Program of Young and Middle Aged Academic and Technological Leaders in Yunnan Province [grant number 2017HB030] and the High Level Innovative One-Ten-Thousand Youth Talents of Yunnan Province [grant number 2020].

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